

LISTING OF THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the present application:

Claim 1 (Currently Amended) A method for fabricating a silicon-on-insulator (SOI) substrate comprising the steps of:

(a) subjecting a Si-containing substrate to a ~~base~~ first oxygen ion implantation step to create a first structure having a damaged implant region within the Si-containing substrate;

(b) subjecting the first structure to a ~~room temperature~~ second oxygen ion implantation step to create a second structure having an amorphized implant region adjacent to said damaged implanted region; and

(c) performing an annealing process on said second structure, wherein at least one of steps (a)-(c) is performed under conditions that are capable of providing an SOI substrate comprising a buried oxide having a breakdown field of greater than 5 MV/cm, with the proviso that when step (a) is selected to achieve said breakdown field the ~~base~~ first oxygen ion implantation step is performed using an oxygen ion dose of about 2.5E17 cm⁻² or less, when step (b) is selected to achieve said breakdown field the ~~room temperature~~ second oxygen ion implantation step is performed at an energy that is about 5 to about 20 % less than an energy used during the ~~base~~ first oxygen ion implantation step, or when step (c) is selected to achieve said breakdown field a pre-annealing soak cycle is employed prior to an internal oxidation step which dissolves non-stoichiometric SiO_x precipitates formed during steps (a) and (b).

Claim 2 (Original) The method of Claim 1 wherein steps (b) and (c) are selected to achieve said breakdown field.

Claim 3 (Original) The method of Claim 1 wherein steps (a)-(c) are selected to achieve said breakdown field.

Claim 4 (Original) The method of Claim 1 wherein step (c) is selected to achieve said breakdown field.

Claim 5 (Original) The method of Claim 1 further comprising providing a patterned masking material or dielectric cap to said Si-containing substrate prior to performing step (a).

Claim 6 (Original) The method of Claim 5 wherein said patterned masking material or dielectric cap is removed after performing step (b) or after performing step (c).

Claim 7 (Currently Amended) The method of Claim 1 wherein the ~~base~~ first oxygen ion implantation step is performed utilizing ~~a single ion implantation step or~~ multiple ion implantation steps.

Claim 8 (Currently Amended) The method of Claim 1 wherein the ~~room temperature~~ second oxygen ion implantation step is performed utilizing ~~a single ion implantation step or~~ multiple ion implantation steps.

Claim 9 (Original) The method of Claim 1 wherein annealing process comprises a ramp-up anneal, an internal oxidation, annealing and a ramp-down step.

Claim 10 (Original) The method of Claim 1 wherein said annealing process forms a surface oxide on said Si-containing substrate.

Claim 11 (Original) The method of Claim 10 further comprising a step of removing said surface oxide from said Si-containing substrate by planarization or selective etching.

Claim 12 (Original) The method of Claim 1 wherein step (a) is selected to achieve said breakdown field and said oxygen ion dose is from about 2.0E17 to about 2.4E17 cm⁻².

Claim 13 (Original) The method of Claim 1 wherein step (a) is performed in an ion beam apparatus that operates at a beam current from about 1 to about 100 millamps and an energy from about 1 to about 10,000 keV.

Claim 14 (Original) The method of Claim 1 wherein step (a) is performed at a substrate temperature from about 100° to about 800°C.

Claim 15 (Original) The method of Claim 1 wherein step (b) is selected to achieve said breakdown field and said energy is off-set to a value from about 6 to about 8 % lower than the energy of said base oxygen ion implantation step.

Claim 16 (Original) The method of Claim 1 wherein step (b) is selected to achieve said breakdown field and said energy is from about 155 to about 165 keV.

Claim 17 (Original) The method of Claim 1 wherein step (b) is performed using an oxygen ion dose from about 1E15 to about 5E15 cm⁻².

Claim 18 (Original) The method of Claim 1 wherein step (b) is performed at a temperature from about 1 Kelvin to about 200°C.

Claim 19 (Original) The method of Claim 1 wherein step (c) is selected to achieve said breakdown field and said annealing process includes a ramp-up step, said pre-annealing soak, said internal oxidation annealing, annealing and a cool-down step.

Claim 20 (Original) The method of Claim 19 wherein said pre-annealing soak is performed at a temperature of about 1250°C or greater.

Claim 21 (Original) The method of Claim 19 wherein said pre-annealing soak is performed for a time period from about 5 minutes to about 5 hours.

Claim 22 (Original) The method of Claim 19 wherein said ramp-up step, said pre-annealing soak, said annealing and said cool-down step are performed in the same or different ambient that comprises an inert gas containing less than 10% oxygen.

Claim 23 (Original) The method of Claim 19 wherein said pre-annealing soak is performed in an ambient containing greater than 30 % oxygen.

Claim 24 (Currently Amended) A method of fabricating a silicon-on-insulator substrate (SOI) comprising the steps of:

(a) subjecting a Si-containing substrate to a base first oxygen ion implantation step to create a first structure having a damaged implant region within the Si-containing substrate;

(b) subjecting the first structure to a ~~room temperature~~ second oxygen ion implantation step to create a second structure having an amorphized implant region adjacent to said damaged implanted region, wherein said ~~room temperature~~ second oxygen ion implantation step is performed at an energy that is about 5 to about 20 % less than an energy used during the base first oxygen ion implantation step; and

(c) performing an annealing process on said second structure, wherein an SOI substrate is provided that comprises a buried oxide having a breakdown field of greater than 5 MV/cm.

Claim 25 (Currently Amended) A method for fabricating a silicon-on-insulator (SOI) substrate comprising the steps of:

(a) subjecting a Si-containing substrate to a base first oxygen ion implantation step to create a first structure having a damaged implant region within the Si-containing substrate;

(b) subjecting the first structure to a ~~room temperature~~ second oxygen ion implantation step to create a second structure having an amorphized implant region adjacent to said damaged implanted region; and

(c) performing an annealing process on said second structure, said annealing process includes a pre-annealing soak cycle employed prior to an internal oxidation step which dissolves non-stoichiometric SiO_x precipitates formed during steps (a) and (b), wherein an SOI substrate is provided that comprises a buried oxide having a breakdown field of greater than 5 MV/cm.

Claim 26 (Currently Amended) A method for fabricating a silicon-on-insulator substrate comprising ~~the steps of~~:

(a) subjecting a Si-containing substrate to a ~~base~~ first oxygen ion implantation step to create a first structure having a damaged implant region within the Si-containing substrate;

(b) subjecting the first structure to a ~~room~~ temperature second oxygen ion implantation step to create a second structure having an amorphized implant region adjacent to said damaged implanted region, said ~~room~~ temperature second oxygen ion implantation step is performed at an energy that is about 5 to about 20 % less than an energy used during the ~~base~~ first oxygen ion implantation step; and

(c) performing an annealing process on said second structure, said annealing process includes a pre-annealing soak cycle employed prior to an internal oxidation step which dissolves non-stoichiometric SiO_x precipitates formed during steps (a) and (b), wherein an SOI substrate is provided comprises a buried oxide having a breakdown field of greater than 5 MV/cm.

Claim 27 (Currently Amended) A method for fabricating a silicon-on-insulator substrate comprising ~~the steps of~~:

(a) subjecting a Si-containing substrate to a ~~base~~ first oxygen ion implantation step to create a first structure having a damaged implant region within the Si-containing substrate, said ~~base~~ first oxygen ion implantation step is performed using an ion dose of about 2.5 cm⁻² or less at an energy of 170 keV or greater;

(b) subjecting the first structure to a ~~room temperature~~ second oxygen ion implantation step to create a second structure having an amorphized implant region adjacent to said damaged implanted region, said ~~room temperature~~ second oxygen ion implantation step is performed at an energy that is about 5 to about 20 % less than an energy used during the ~~base~~ first oxygen ion implantation step; and

(c) performing an annealing process on said second structure, said annealing process includes a pre-annealing soak cycle employed prior to an internal oxidation step which dissolves non-stoichiometric SiO_x precipitates formed during steps (a) and (b), wherein an SOI substrate is provided comprises a buried oxide having a breakdown field of greater than 5 MV/cm.